Amendments to the Claims

1. (CURRENTLY AMENDED) A thin film patterning arrangement ~~(6)~~, comprising a substrate ~~(1)~~ and barriers ~~(3)~~ arranged to partition a surface of the substrate ~~(1)~~ into sub-areas ~~(5)~~, characterised in that at least said surface is of polymeric material, and said surface is at least partly coated with at an least partly inorganic coating ~~(2)~~.

2. (CURRENTLY AMENDED) An arrangement ~~(6)~~ according to claim 1, wherein said at least partly inorganic coating ~~(2)~~ comprises 100 % inorganic material.

3. (CURRENTLY AMENDED) An arrangement ~~(6)~~ according to claim 1, wherein said at least partly inorganic coating ~~(2)~~ comprises at least 5 % inorganic material.

4. (CURRENTLY AMENDED) An arrangement ~~(6)~~ according to ~~any of the preceding claims,~~claim 1, wherein said at least partly inorganic coating ~~(2)~~ comprises at least two separate coating materials.

5. (CURRENTLY AMENDED) An arrangement ~~(6)~~ according to ~~any of the preceding claims~~claim 1, wherein after a surface treatment, a difference in advancing contact angle of at least 10 degrees between the surface of said at least partly inorganic coating ~~(2)~~ and the surfaces of said barriers ~~(3)~~ is established.

6. (CURRENTLY AMENDED) An arrangement ~~(6)~~ according to ~~any of the preceding claims~~claim 1, wherein said at least partly inorganic coating ~~(2)~~ is more than 70% transparent.

7. (CURRENTLY AMENDED) A method for producing a thin film patterning arrangement ~~(6)~~, comprising:

- supplying a substrate ~~(1)~~ with at least a surface of polymeric material,
- coating at least a part of said surface of said substrate ~~(1)~~ with an at

least partly inorganic coating ~~(2)~~, and

- depositing barriers ~~(3)~~ on said at least one coated surface.

8. (CURRENTLY AMENDED) A method according to claim 7, further comprising:

- subjecting said at least partly inorganic coating ~~(2)~~ and said barriers ~~(3)~~ to a surface treatment.

9. (ORIGINAL) A method according to claim 8, wherein said surface treatment comprises plasma treatment.

10. (CURRENTLY AMENDED) A thin film device comprising a thin film patterning arrangement (6) according to ~~any of the claims 1-6~~claim 1, or a thin film patterning arrangement obtainable by the method according to ~~any of the claims 7 to 9~~claim 7, further comprising thin film material ~~(4)~~ deposited on at least part of said sub-areas ~~(5)~~.

11. (CURRENTLY AMENDED) A thin film device according to claim 10, wherein said thin film material ~~(4)~~ forms at least one thin film pattern selected from the group comprising optical patterns, conductor patterns, insulator patterns, semiconductor patterns and combinations thereof.

12. (ORIGINAL) A thin film device according to claim 11, wherein said thin film pattern is an optical pattern and said device is a colour filter.

13. (CURRENTLY AMENDED) A method for manufacture of a thin film device, comprising:

- providing a thin film patterning arrangement ~~(6)~~ according to ~~any of the claims 1 to 6~~claim 1, or a thin film patterning arrangement ~~(6)~~ obtainable by a method according to ~~any of the claims 7 to 9~~claim 7, and

- depositing at least one thin film material ~~(4)~~ on at least part of said sub-areas ~~(5)~~.

14. (CURRENTLY AMENDED) A method according to claim 12 wherein said depositing of thin film material ~~(4)~~ comprises:

- ink jet printing of a liquid comprising said thin film material ~~(4).~~

15. (CURRENTLY AMENDED) A display device comprising a thin film patterning arrangement ~~(6)~~ according to ~~any of the claims 1 to 6,~~claim 1 a thin film patterning arrangement ~~(6)~~ obtainable by a method according to ~~any of the claims 7 to 9~~claim 7, a thin film device according to ~~any of the claims 10 to 12~~claim 10, or a thin film device obtainable by a method according to ~~any of the claims 13 to 14~~claim 13.